ABSTRACT

, , ,

A conventional silsesquioxane derivative has the problems that the functional groups are restricted and the chemical structure is not readily controlled and that it is expensive. The present inventors have developed a process for producing a silsesquioxane derivative at a high yield by a simple process in order to solve such problems. The novel silsesquioxane derivative according to the present invention is controlled in a structure thereof and has a functional group, which is excellent in 10 reactivity with a target compound, to be modified. The present invention relates to a production process for a silsesquioxane derivative represented by Formula (2), characterized by using a silicon compound represented by Formula (1). In Formula (1) and Formula (2), R is a 15 group selected from hydrogen, alkyl, aryl and arylalkyl; ${\tt M}$ is a monovalent alkaline metal atom; at least one of ${\tt Y}$ is a group represented by Formula (3), and the remainder of Y is hydrogen; R^1 and R^2 in Formula (3) represent the same group as defined for R; and Z is a functional group 20 or a group having a functional group.

$$\begin{bmatrix} R & Si - O & Si -$$